

NS6130-10 -1450

TERBIUM IRON Sputtering Target

Quick Facts

Product	:	Terbium Iron Sputtering Target
Stock No	:	NS6130-10 -1450
CAS	:	84059-28-9
Molecular Formula	:	Tb-Fe
Form	:	Solid

Technical Specification

Diameter	Thickness	Purity
50.8 mm \pm 1mm	3 mm \pm 0.5mm	99.9%

Tb-Fe sputtering target deposits thin films of terbium iron alloy onto substrates. The sputtering process creates uniform, adherent films that enhance magnetic properties. It is used in thin film deposition for magnetic and electronic applications, magnetic storage media, spintronics, sensors, and research into new materials and technologies.

Application:

- Thin Film Deposition
- Magnetic storage
- Spintronics
- Sensors
- Research

